

ABSTRACT OF THE DISCLOSURE

An exposure method for exposing the same location of the substrate a plurality of times through a mask formed with a pattern while changing the amounts of exposure with respect to a substrate by pulse light at a plurality of positions in the direction (Z-direction) in which the substrate being exposed is irradiated by the pulse light, wherein the energy of the pulse light is set so that the cumulative number of pulses at the position giving the maximum amount of exposure in the plurality of positions becomes at least the predetermined number of pulses.